

# A 25-ns 4-Mbit CMOS SRAM with Dynamic Bit-Line Loads

FUMIO MIYAJI, YASUO MATSUYAMA, YOSHIKAZU KANAISHI, KATSUNORI SENOH, TAKASHI EMORI, AND YOSHIAKI HAGIWARA, MEMBER, IEEE

A 4-Mbit CMOS SRAM with a 25-ns access time has been developed. The RAM was fabricated using a 0.5- $\mu\text{m}$  poly and double-aluminum CMOS technology and was assembled in a 400-pin DIP. A small cell size of  $3.6 \times 5.875 \mu\text{m}^2$  and a chip area of  $16 \times 17.41 \text{ mm}^2$  were obtained. A fast address access time of 25 ns at a single 3.3-V supply voltage has been achieved using our newly developed dynamic bit-line load (DBL) circuit scheme incorporated with an access transistor detector (ATD), divided word-line structure (DWT), sense amplifier, and low-noise output circuit approach. A low standby current of 46 nA at 40 MHz and low standby currents of 70  $\mu\text{A}$  and 5  $\mu\text{A}$  (CMOS) were also attained.

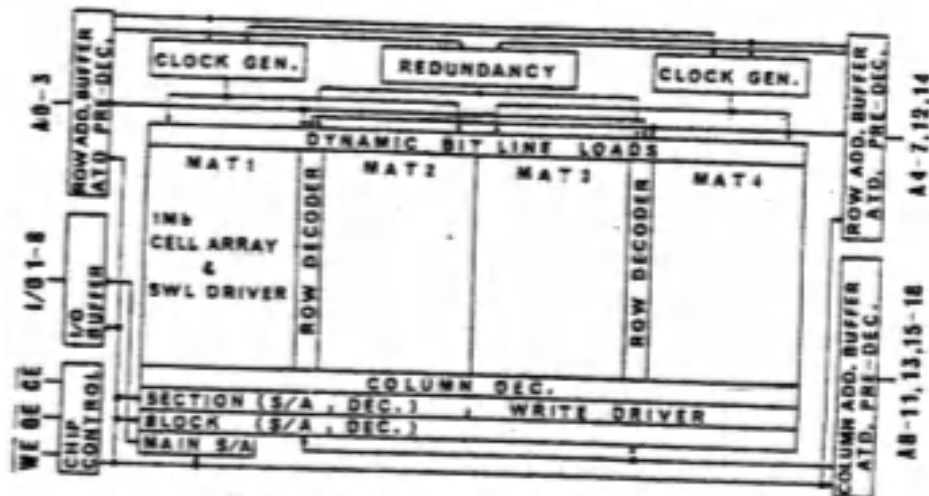


Fig. 1. Block diagram of the RAM.

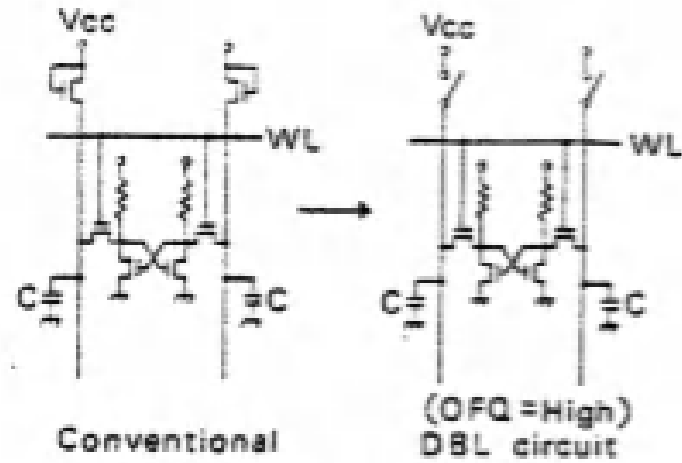


Fig. 6. Concept of DBL.

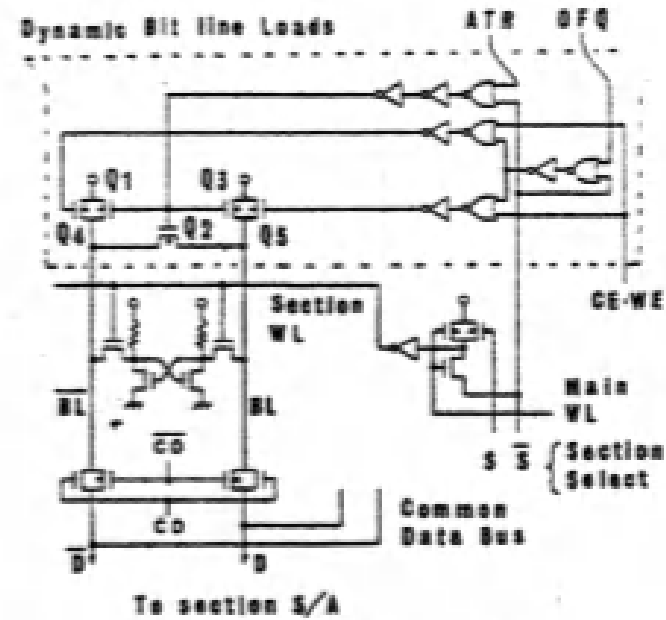


Fig. 4. DBL circuit.

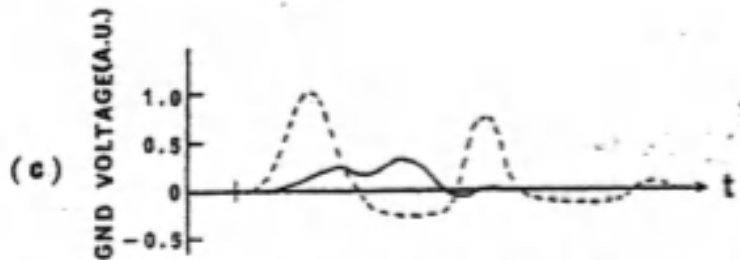
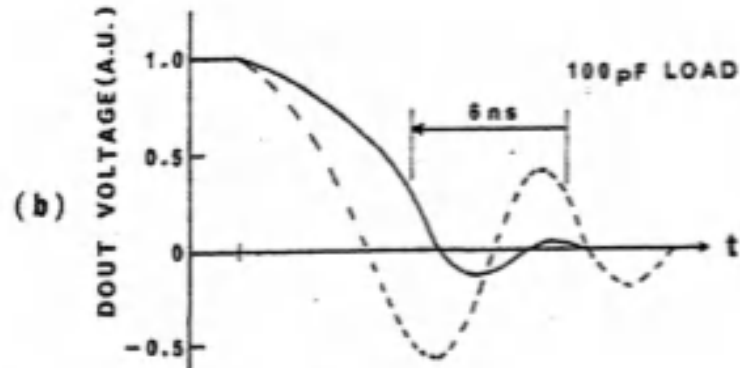
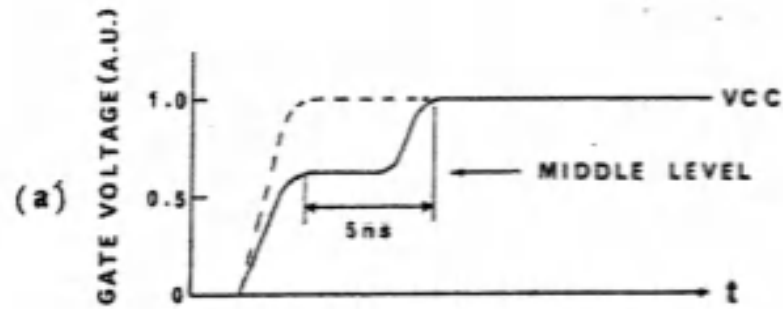


Fig. 9. Waveforms of proposed (solid line) and conventional (dotted line) output circuits: (a) gate bias, (b) data output, and (c) GND bounce.

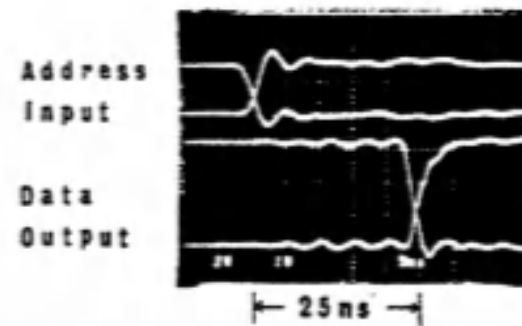


Fig. 10. Waveforms of the address access time.

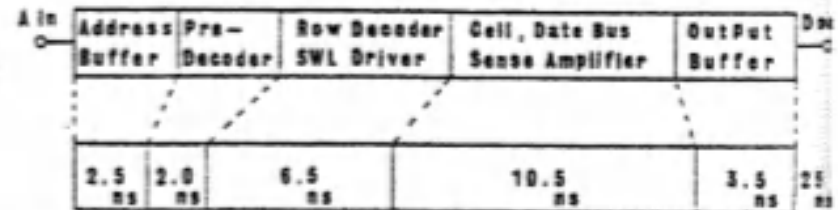


Fig. 11. Components of the access time in the 4-Mbit SRAM.

against collection of charge carriers from the substrate, the retrograde P-well with a  $1.2\text{-}\mu\text{m}$  junction depth is used. This technology utilizes a double-level polysilicid and a double-level aluminum layer. The gate oxide thickness is 11 nm. The first polysilicon layer, tungsten polycide, is used for gate electrodes, and the second polysilicid layer is used for high-resistance memory cell loads. The first aluminum is used for GND lines in the memory array and the main word lines to reduce the delay time. The second aluminum is used for the bit lines to reduce the stray capacitance. The minimum contact and via hole sizes

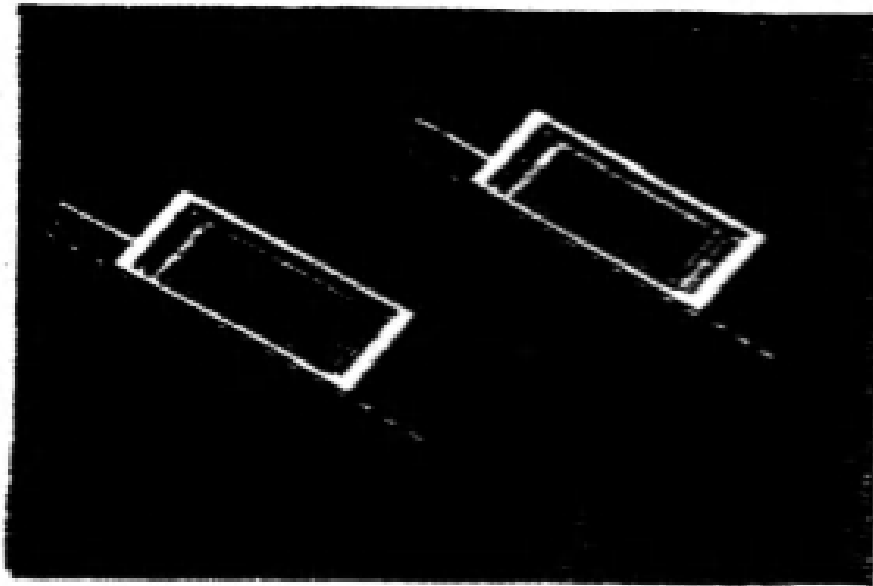


Fig. 12. 4-Mbit SRAM assembled into a 400-mil DIP.

TABLE I  
TYPICAL CHARACTERISTICS

Organization	512KW x 8bit
Chip size	7.46 x 17.41 mm <sup>2</sup>
Cell size	3.6 x 5.875 um <sup>2</sup>
Power supply	3.3V
Address access time	25ns
Active current	33mA at 10MHz 46mA at 40MHz
Standby current	70uA at V <sub>DD</sub> =2.2V
Package	32Pin, 400mil DIP
Redundancy	8 rows

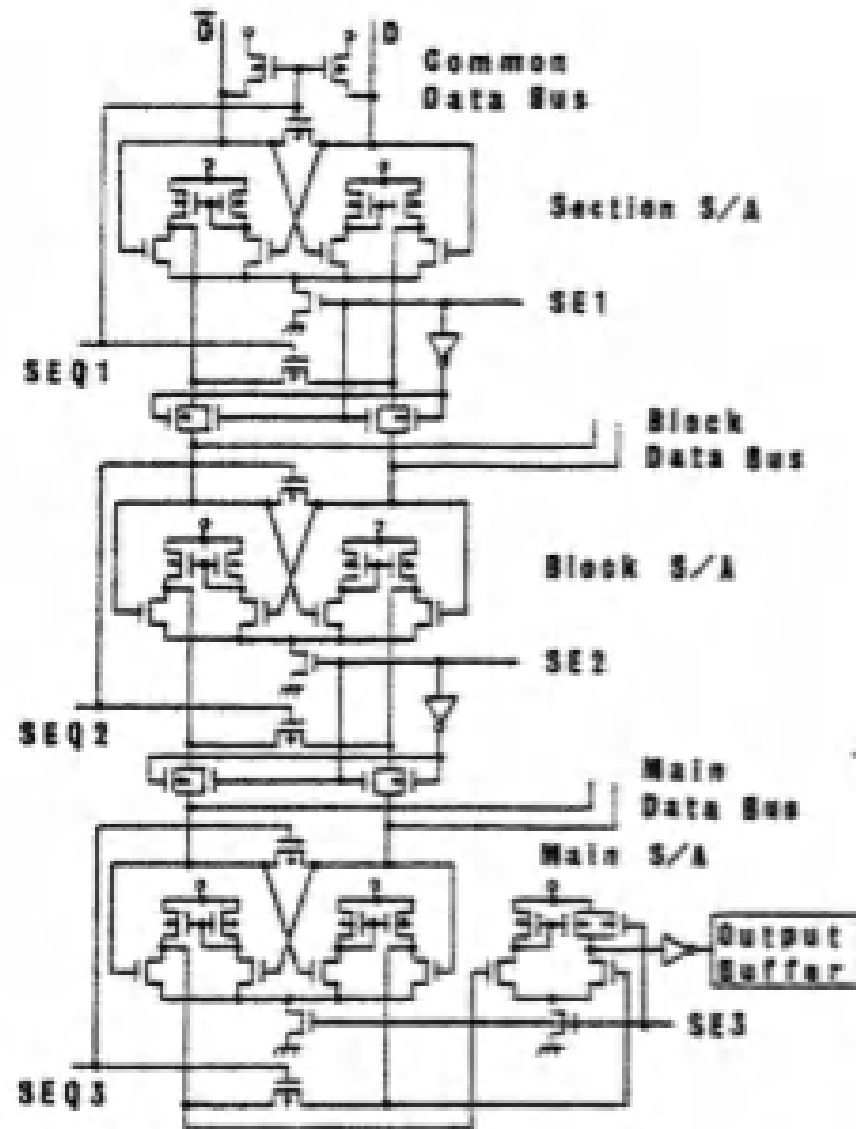


Fig. 7. Three-stage sense amplifier circuit.